

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of : Akira IKUSHIMA, Kazuya SAITO, Takashi MIURA
and Shogo NASUDA
For : METHOD OF PROCESSING A SILICA GLASS
FIBER
Group Art Unit : 1731
Examiner : John Hoffmann
Docket : ADACHI P163USP2



#4
8-16-01

The Commissioner of Patents and Trademarks
Washington, D.C. 20231

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

In connection with this matter, the Applicant hereby attaches one (1) United States Patent Office Form PTO-1449 and copies of the information listed in the enclosed PTO-1449 Form, unless otherwise indicated on such Form.

Copies of the information being made of record in this Information Disclosure Statement is not being submitted, as permitted by 37 CFR 1.98(d), as this information was previously cited by or submitted to the United States Patent and Trademark Office in a prior application, namely United States Patent Application Serial No. 09/351,951 filed July 12, 1999 and that prior application is properly identified in this statement and relied upon for an earlier filing date under 35 USC 120.

In the event that there are any fee deficiencies or additional fees are payable, please charge the same or credit any overpayment to our Deposit Account (Account No. 04-0213).

Respectfully submitted,

A handwritten signature in black ink, appearing to read "Michael J. Bujold".

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INFORMATION DISCLOSURE
STATEMENT BY APPLICANT
(Use several sheets if necessary)

Atty Docket: ADACHI P163USP2

Examiner: John Hoffmann

Group: 1731

Applicant: Akira IKUSHIMA, Kazuya SAITO, Takashi
MIURA and Shogo NASUDA

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Sub-Class	Filing Date, if Appropriate
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16821 U.S. PTO
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"Temperature Dependence of the E⁺ Center Creation in Silica Glasses", *Physica Status Solidi (b)*, vol. 147, No. 1, 1988, pp.k1-k4.